



Application Number

10/688,047

"Chung Foong Tan et al.

10/17/03

Group Art Unit

JAN 29 2004

*(Use several sheets if necessary)*

~~CONFIDENTIAL~~

RUN DATE  
 IF APPROPRIATE

### Translation

**NO**

## MG

"Effects of end-of-range dislocation loops on transient enhanced diffusion of indium implanted in silicon" T. Noda et al, Journal of Applied Physics, Vol. 88, No. 9, Nov. 2001, pp. 4980-4984.

MG

"Enhanced electrical activation of indium coimplanted with carbon in a silicon substrate," H. Bondinov et al., Journal of Applied Physics, Vol. 86, No. 10, pp. 5909-5911, Nov. 15, 1999.

EXAMINER

Maria Guerrero

DATE CONSIDERED

4-12-05

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

## EXAMINER

Maria C. Gennaro

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4-12-05

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U. S. PATENT DOCUMENTS

[illegible]

# FOREIGN PATENT DOCUMENTS

[illegible]

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

MG

"Elimination of secondary defects in preamorphized Si by  $C^+$  implantation", Satoshi Mishikawa et al., Applied Physics Letters, 62(3), Jan. 18, 1993, pp. 303-305.

M.C.

"Removal of end of range defect in  $\text{Ge}^+$  pre-amorphized Si by carbon ion implantation", Peng-Shiu Chen et al., J. Appl. Phys., Vol. 85, No. 6, March 15, 1999, pp. 3114-3119.

## ΕΛΛΗΝΙΑ

Yara Guevara

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